

IN THE U.S. PATENT AND TRADEMARK OFFICE

Jun S. LEE

Conf.: 5244

Serial No.:

Applicant:

09/722,583

Art Unit:

Filed:

November 28, 2000

Examiner:

B. Kebede CEHIER 2800

For:

METHOD FOR FABRICATING CAPACITOR OF

SEMICONDUCTOR DEVICE

AMENDMENT UNDER 37 C.F.R. §1.111

Assistant Commissioner for Patents Washington, DC 20231

February 5, 2003

465-758P

Sir:

In response to the Office Action mailed November 7, 2002 (Paper No. 14), following amendments and remarks are respectfully submitted in

02/12/2003 ASEAR DECISION With the above-identified application:

84.00 CH

IN THE CLAIMS:

Please rewrite claims 1 and 4 as follows:

1. (Amended) A method for fabricating a capacitor of a semiconductor device comprising:

depositing a nitride film and an oxide film over a substrate, the oxide film being deposited on the nitride film/by chemical vapor deposition;

sequentially etching the oxide film and the nitride film using a patterned photoresist as a mask;